	Туре	Hits	Search Text	DBs	Time Stamp	o m m e	ef in	Er ro rs
1	BRS	3477 8	heating same temperature same (Al or aluminum or titanium ot Ti or tantalum or Ta or mask)	USPAT; EPO; JPO; DERWENT; IBM TDB	2002/01/17 11:01			0
2	BRS	1356	heating same temperature same (Al or aluminum or titanium ot Ti or tantalum or Ta or mask) same semiconductor	USPAT; EPO; JPO; DERWENT; IBM TDB	2002/01/17 10:54			0
3	BRS	853	(heating same temperature same (AI or aluminum or titanium ot Ti or tantalum or Ta or mask) same semiconductor) and @pd<=19970120	USPAT; EPO; JPO; DERWENT; IBM TDB	2002/01/17 11:59			0
4	BRS	14	(heating same temperature same ((Al or aluminum or titanium ot Ti or tantalum or Ta) adj5 mask)) and 438/\$.ccls.	USPAT; EPO; JPO; DERWENT; IBM TDB	2002/01/17 11:04			0
5	BRS	48	heating same temperature same ((Al or aluminum or titanium ot Ti or tantalum or Ta) adj5 mask)	USPAT; EPO; JPO; DERWENT; IBM TDB	2002/01/17 11:54			0
6	BRS	13	heating same temperature same ((Al or aluminum or titanium ot Ti or tantalum or Ta) adj5 mask) same etching	USPAT; EPO; JPO; DERWENT; IBM TDB	2002/01/17 11:58			0
7	BRS	141	temperature same ((Al or aluminum or titanium ot Ti or tantalum or Ta) adj5 mask) same etching	USPAT; EPO; JPO; DERWENT; IBM TDB	2002/01/17 12:32			0
8	BRS	111	(temperature same ((Al or aluminum or titanium ot Ti or tantalum or Ta) adj5 mask) same etching) and @pd<=19970120	USPAT; EPO; JPO; DERWENT; IBM TDB	2002/01/17 12:00			0
9	BRS	37	temperature same ((Al or aluminum or titanium ot Ti or tantalum or Ta) adj5 mask) same ((dry or plasma) adj etching)	USPAT; EPO; JPO; DERWENT; IBM TDB	2002/01/17 12:23			0
10	BRS	0	temperature same ((Al or aluminum or titanium ot Ti or tantalum or Ta) adj5 mask) same etching same "critical dimension"	USPAT; EPO; JPO; DERWENT; IBM TDB	2002/01/17 12:33			0